EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	28	("20020025019"|"20020177076"|"4878086"|"5194344"|"5194346"|"5308741"|"5384219"|"5851704"|"5906910"|"5908718"|"6040892"|"6498105"|"6522389"|"6628372").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/12/30 13:32
L2	0	(kenvin near4 deusman).inv.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:40
L3	0	(kenvin near4 duesman).inv.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:40
L4	175	(kevin near4 duesman).inv.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:40
L5	9	4 and first adj4 (mask or reticle or pattern$4) and second adj3 (mask or reticle or pattern$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:41
L6	5	4 and (first adj4 (mask or reticle or pattern$4) and second adj3 (mask or reticle or pattern$4)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:42
L7	6	(randal near5 chance).inv. and (second adj3 (mask or reticle or pattern$4)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:43
L8	28	(($4lithograph$4 or exposure) and (second adj3 (mask or pattern$4 or reticle)) near6 (dispos$4 or plac$4 or position$4) near5 (between near6 (first adj4 (mask or reticle or pattern$5) near6 (wafer or substrate or object or photosensitive or support$4 or stage)))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:47

L9	18	(($4lithograph$4 or exposure) and (second adj3 (mask or pattern$4 or reticle)) near6 (dispos$4 or plac$4 or position$4) near5 (between near6 (first adj4 (mask or reticle or pattern$5) near6 (wafer or substrate or object or photosensitive)))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:58
L10	9	(($4lithograph$4 or exposure) and (light or radiation or beam or ray) and (second adj3 (mask or pattern$4 or reticle)) near4 (dispos$4 or plac$4 or position$4) near5 ("between" near4 (first adj4 (mask or reticle or pattern$5) near4 (wafer or substrate)))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 13:57
L11	4	(($4lithograph$4 or exposure) and (second adj3 (mask or reticle)) near6 (dispos$4 or plac$4 or position$4) near5 (between near6 (first adj4 (mask or reticle) near6 (wafer or substrate or object or photosensitive)))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 14:00
L12	3	(($4lithograph$4 or exposure) and (light or radiation or ray or beam) and (second adj3 (mask or reticle)) near6 (dispos$4 or plac$4 or position$4) near5 (between near6 (first adj4 (mask or reticle) near6 (wafer or substrate or object or photosensitive)))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/30 14:00